

## Refine Search

### Search Results -

Terms	Documents
L15 and L9	4

Database:

US Pre-Grant Publication Full-Text Database  
 US Patents Full-Text Database  
 US OCR Full-Text Database  
 EPO Abstracts Database  
 JPO Abstracts Database  
 Derwent World Patents Index  
 IBM Technical Disclosure Bulletins

Search:

L16 ▲  
▼





### Search History

DATE: Thursday, September 21, 2006    [Purge Queries](#)    [Printable Copy](#)    [Create Case](#)

#### Set Name Query

side by side

#### Hit Count Set Name

result set

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

<u>L16</u>	L15 and L9	4	<u>L16</u>
<u>L15</u>	L4 and (third near5 (dielectric or insulat\$)).clm.	5295	<u>L15</u>
<u>L14</u>	L4 and (remov\$ near6 photoresist near8 expos\$ near8 metal).clm.	60	<u>L14</u>
<u>L13</u>	l9 and l12	7	<u>L13</u>
<u>L12</u>	L4 and (remov\$ near6 photoresist near8 expos\$ near8 metal)	366	<u>L12</u>
<u>L11</u>	L10 and L9	16	<u>L11</u>
<u>L10</u>	L4 and (third near5 (dielectric or insulat\$))	12731	<u>L10</u>
<u>L9</u>	L8 and (mask near12 photoresist)	139	<u>L9</u>
<u>L8</u>	L7 and (ARC or antireflective)	282	<u>L8</u>
<u>L7</u>	L6 and ((expos\$ or etch\$) near10 metal)	1604	<u>L7</u>
<u>L6</u>	L4 and (etch\$ near12 stack\$)	3016	<u>L6</u>
<u>L5</u>	L4 and (etch \$ near12 stack\$)	1	<u>L5</u>
<u>L4</u>	(metal line or wire)	1885028	<u>L4</u>
<u>L3</u>	"Kwang" near3 "Ok" near3 "Kim".inv.	11	<u>L3</u>

L2 "Yu" near3 "Chang" near3 "Kim".inv.

12 L2

L1 "yu near3 Chang near3 Kim".inv.

0 L1

END OF SEARCH HISTORY